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Patent Plaques

JP4229607A2: MAGNETICALLY SOFT THIN FILM AND ITS MANUFACTURE

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Country: **JP Japan**

Kind:

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KIMURA FUJIMI**Applicant(s): **TDK CORP**
[News, Profiles, Stocks and More about this company](#)Issued/Filed Dates: **Aug. 19, 1992 / April 25, 1991**Application Number: **JP1991000122515**IPC Class: **H01F 10/16; C25D 7/00; H01F 41/26;**Priority Number(s): **Aug. 9, 1990 JP1990000210741**



Abstract: **Purpose:** To realize a magnetically soft thin film whose coercive force is low, whose saturation flux density is high and whose magnetostriction is low by means of an electroplating method without performing the complicated control of a plating bath.

Constitution: A magnetically soft thin film which is composed mainly of Co, whose content of Fe is 2 to 15wt.% and whose content of S is 500 to 2000ppm is formed by using a plating bath containing the following: one or more kinds of compounds selected from a compound provided with a sulfinic acid group or its salt, a sulfonic acid group or its salt, a sulfonimide group or a sulfonamide group, from thiourea-based compound and mercaptodicarboxylic acid; Co(II) ions; and Fe(II) ions. Since S does not exist as ions in the plating bath, the plating bath can be controlled easily in the same manner as a binary plating bath.

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Other Abstract Info: **CHEMABS 118(06)051062J CAN118(06)051062J DERABS C92-326518 DERC92-326518**

Foreign References: (No patents reference this one)

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